`						
L Number	Hits	Search Text	DB	Time stamp		
1	960	etch\$3 same silicide and ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") and (HCl Cl2 "Cl.sub.2") and (CO H2 "H.sub.2" N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO;	2003/12/03 20:44		
2	210	etch\$3 same silicide and ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2"))	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:07		
3	50	etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:07		
4	20	etch\$3 same silicide same ((CF4 "CF.sub.4") same (Cl2 "Cl.sub.2") same (N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:07		
5	10	etch\$3 same silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:08		
6	8	etch\$3 with silicide same ((CF4 "CF.sub.4") with (CI2 "Cl.sub.2") with (N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:19		
7	2	(etch\$3 same silicide same ((CF4 "CF.sub.4") with (CI2 "Cl.sub.2") with (N2 "N.sub.2")) not (etch\$3 with silicide same ((CF4 "CF.sub.4") with (CI2 "Cl.sub.2") with (N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:21		
8	10	(etch\$3 same silicide same ((CF4 "CF.sub.4") same (Cl2 "Cl.sub.2") same (N2 "N.sub.2"))) not (etch\$3 same silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:27		
9	6	((etch\$3 same silicide same ((CF4 "CF.sub.4") same (Cl2 "Cl.sub.2") same (N2 "N.sub.2"))) not (etch\$3 same silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/03 20:31		
10	30)) and (sidewall passi\$7) (etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCI CI2 "CI.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2"))) not (etch\$3 same silicide same ((CF4 "CF.sub.4") same (CI2 "CI.sub.2") same (N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:31		
12	0	((ctch\$3 with silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCI Cl2 "CI.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2")) not (etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCI Cl2 "CI.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:45		
11	16	otch\$3 with silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCI Cl2 "CI.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:47		

13	22	etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3"	USPAT;	2003/12/03 20:47
		SF6 "SF.sub.6") with (HCI Cl2 "Cl.sub.2") with (CO H2	US-PGPUB;	
		"H.sub.2" N2 "N.sub.2"))	EPO; JPO;	
1 1	Í		DERWENT;	1
			IBM_TDB	
14	6	(etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3"	USPAT;	2003/12/03 20:47
[[SF6 "SF.sub.6") with (HCI CI2 "Cl.sub.2") with (CO H2	US-PGPUB;	[
1		"H.sub.2" N2 "N.sub.2"))	EPO; JPO;	
	İ) not (etch\$3 with silicide same ((CF4 "CF.sub.4" NF3	DERWENT;	
		"NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO	IBM_TDB	
		H2 "H.sub.2" N2 "N.sub.2"))		
)	j	

L Number	Hits	Search Text	DB	Time stamp
1	750	etch\$3 same (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) and ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same	USPAT; US-PGPUB; EPO; JPO;	2003/12/03 21:05
		(CO H2 "H.sub.2" N2 "N.sub.2" passi\$7))	DERWENT; IBM_TDB	2002/42/22 24-42
2	593	etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) and ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2" passi\$7))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 21:10
3	104	etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2" passi\$7))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 21:05
4	58	etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) with ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2" passi\$7))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 21:10
5	15	etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) with ((CF4 "CF.sub.4") with (CI2 "Cl.sub.2") with (N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 21:09
6	43	(etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) with ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2" passi\$7))) not (etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) with ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 21:09